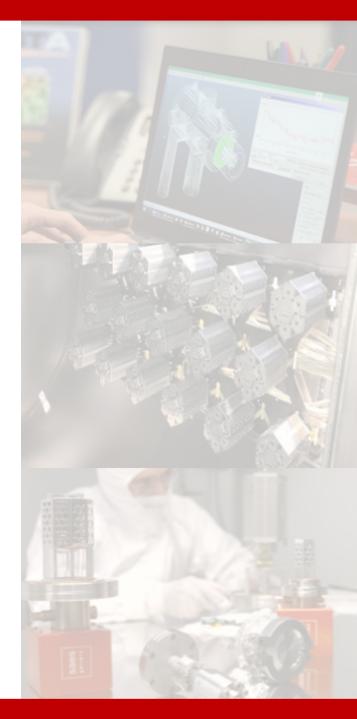


Beampipes for GW Telescopes 2023



CERN, 27th-29th March 2023



Commissioning of the vacuum system

- Rough pumping (from atmospheric pressure to 10⁻¹ mbar)
- HV pumping (from HV to UHV range)
- UHV pumping at RT





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Possible ZAO[®] NEG-based pumping approaches for ET

HV Pumping during bakeout

ZAO «HV» version - HV + UHV pumping solution

- This ZAO version can be used while the outgassing is larger (process pump)
- The same pump can be used to deliver large pumping speed at regime to meet the pressure target
- Compared to «Z», «HV» version of ZAO has more capacity and less pumping speed within the same dimension

UHV Pumping after bakeout

ZAO «Z» version – UHV pumping solution

- This ZAO version can be used to release the maximum pumping speed after the baking
- Compared to «HV», «Z» version of ZAO has more pumping speed and less capacity within the same dimension

NEG cartridge based pumps

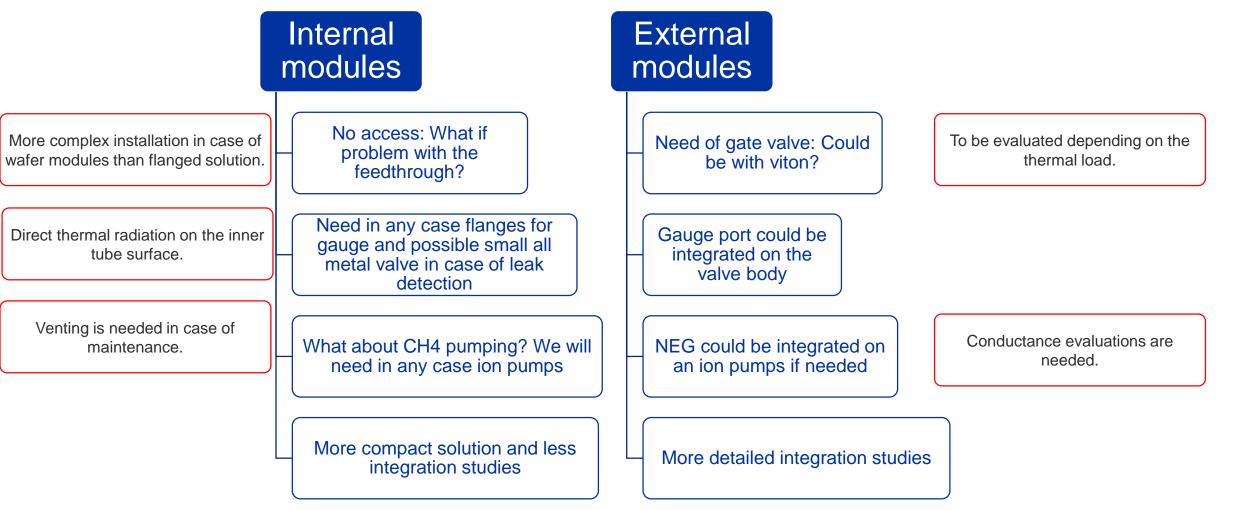
Pressure requirements for ET (TBD)

Gas	Goal P _{ET} [mbar]
H ₂	1 x 10 ⁻¹⁰
CH ₄	1.6 x 10 ⁻¹²
СО	1.9 x 10 ⁻¹²
CO ₂	2 x 10 ⁻¹²
H ₂ O	2 x 10 ⁻¹¹ (Final after bakeout cycle)

Example of outgassing rate per cm² Material Η, CH₄ CO **CO**₂ SS (vacuum fired – Baked 1.0.10-14 2.0.10-17 2.0.10-17 **3.5**·**10**⁻¹⁷ 24h@250C) Mild steel (Baked @ <100C for 20d) 7.5·10⁻¹⁶ < 1.0.10-17 < 1.0·10⁻¹⁶ < 5.10-17



NEG cartridges based pump Best integration strategy?



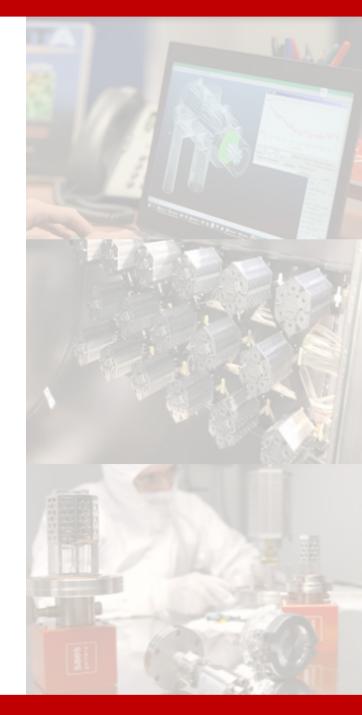




STANDARD PUMPS

- CapaciTorr
- Wafer Module









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CapaciTorr

- NEG Pump only
- CapaciTorr «Z» family → UHV application
- Getter alloy: ZAO UHV (sintered)
- Flange from CF40 to CF200
- Nude configuration
- Working @RT
- From 100 to 3500 l/s for H₂







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CapaciTorr

- CapaciTorr «HV» family → for HV application
 - Higher capacity;
 - In-body (or nude) solution
 - Working @ 200°C (or RT)
- Getter alloy: ZAO HV (sintered)
- Flange from CF40 to CF200
- From 200 to 2100 l/s for H_2







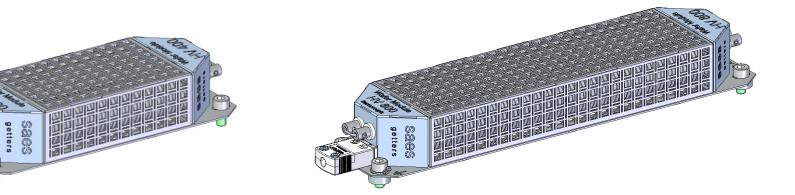


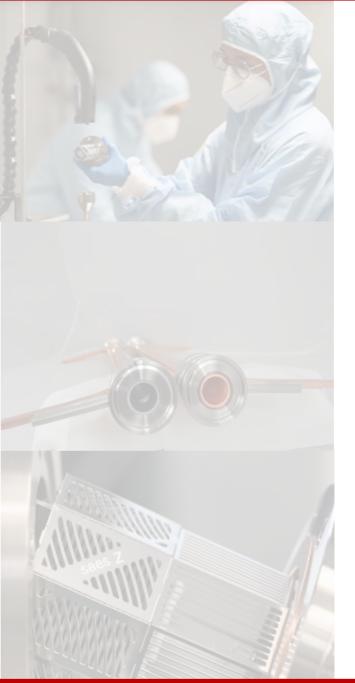


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Wafer Module

- NEG Pump without flange
- HV/UHV application (*ZAO* HV/UHV sintered getter alloy)
- Feedthrough flange and in-vacuum cabling available
- Models with thermocouple available
- From 400 to 1400 l/s for H₂

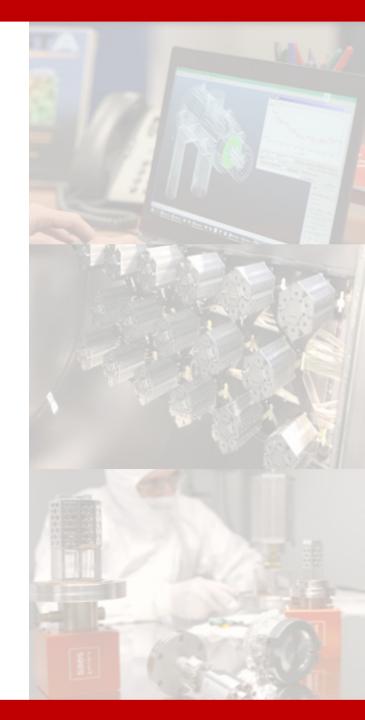




CUSTOM PUMPS

Examples







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40 x CapaciTorr Z 200 Cartridge/CF350

- Pumping speed target 7500 I/s for H₂
- Customer's CF350 special body design;
- n. 40 cartridge CapaciTorr Z 200
- n. 2 feedthroughts 4 pin 10 A

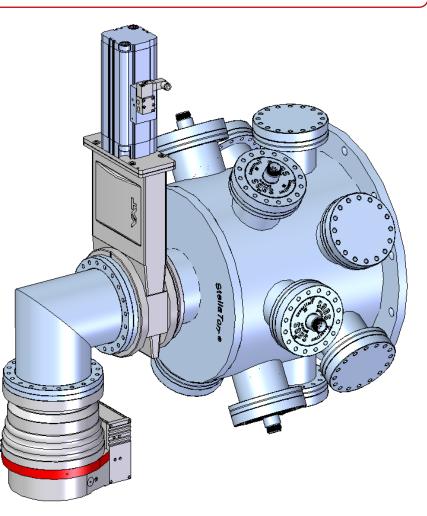




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StellaTorr 2x6xC2100HV/DN400

- The solution allows the installation of 6 or 12 C 2100 HV o CT HV NBI cartridges.
- Body geometry discussed with the customer
- Gate valve, TMP e accessories could have been supplied by SAES or not.

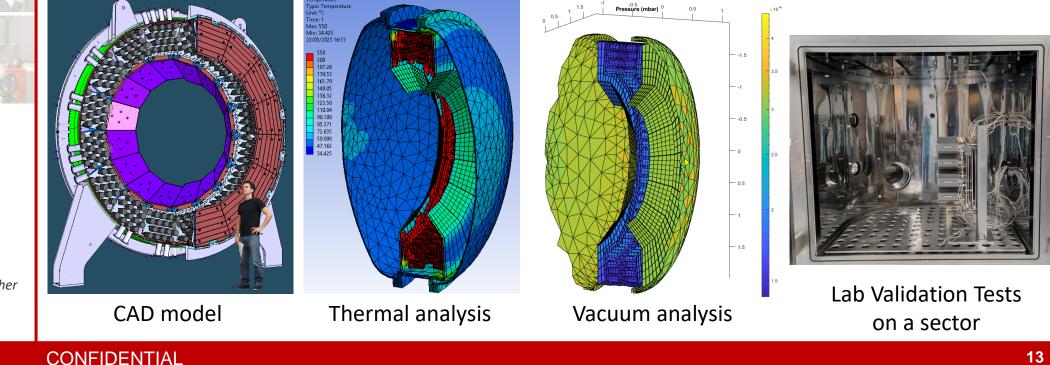




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SPIDER

- Pumping system for SPIDER Neutral Beam Injector experiment at RFX for ITER
- Up to 512 NEG cartridges installed \rightarrow pumping up to 330 m3/s for H2 @e-4 mbar
- Largest NEG pumping system in the world
- Several studies to determine optimal positioning of the pumps
- Thermal and vacuum studies closely linked
- Power supply, electronics and SW integrated within the overall experiment control system



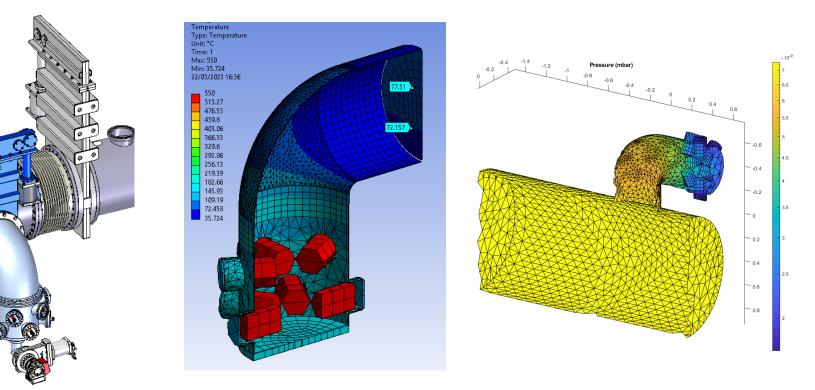


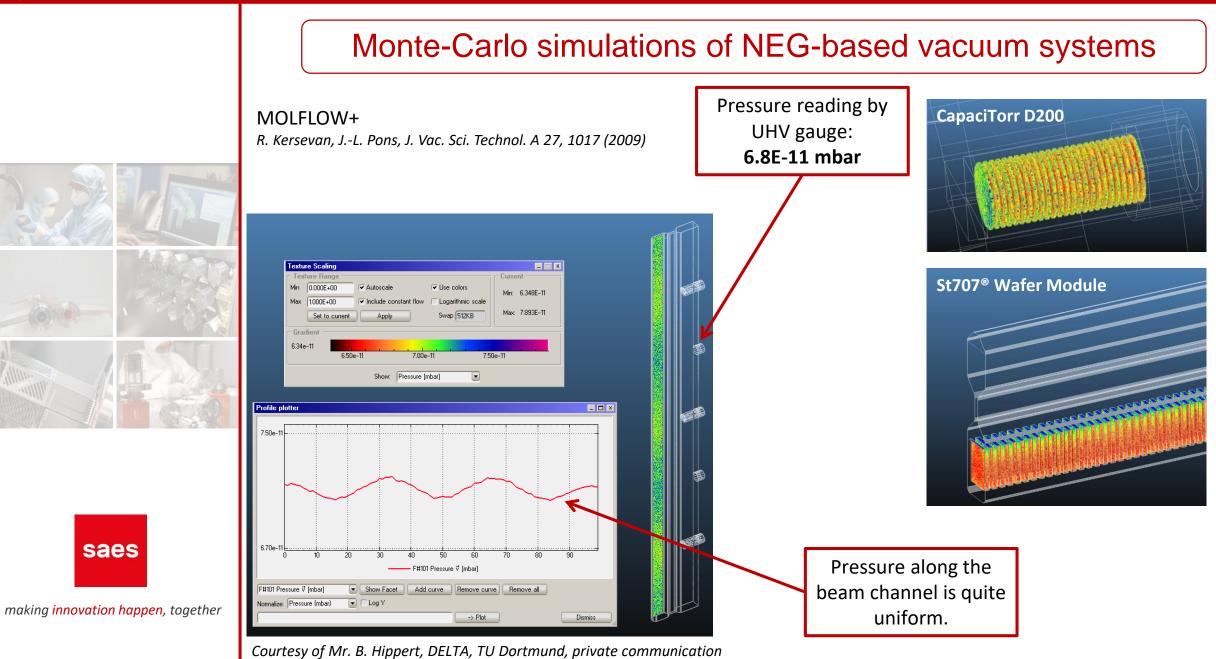


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VIRGO

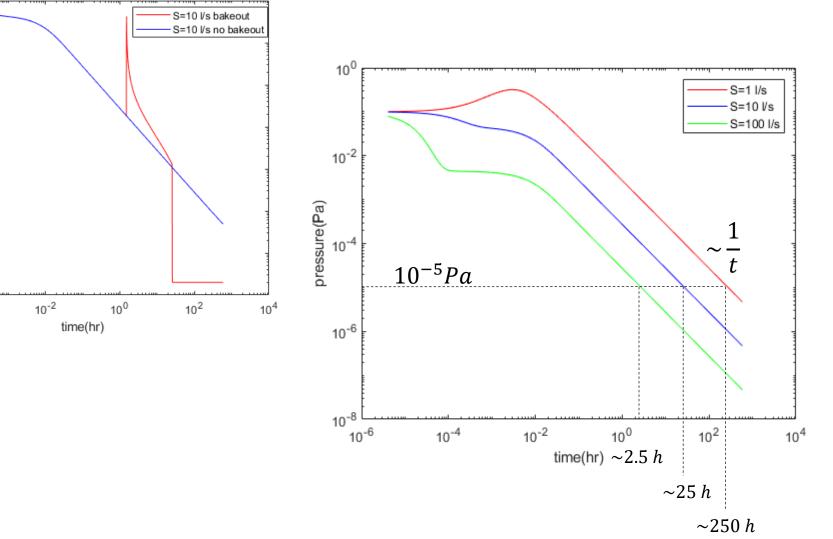
- Pumping enhancement module for Virgo
- CAD project, thermal and vacuum simulation closely linked in iterative process
- Various configurations tested (straight tube, angled elbow, continuous, Tee, etc)
- Best solution chosen for ideal compromise between gate valve T and max pumping

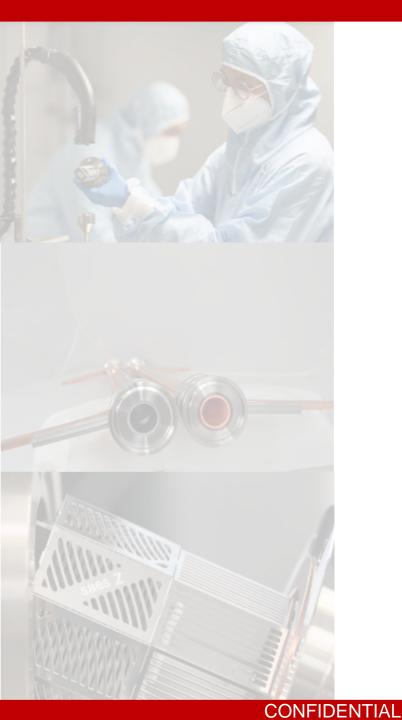




10-10⁻² 10⁻³ (Pa) 10⁻⁴ 10⁻⁵ 10⁻⁵ 10⁻⁶ 10⁻⁷ 10⁻⁸ 10⁻⁶ 10⁻⁴ 10⁻² 10⁰ 10² time(hr) saes making innovation happen, together

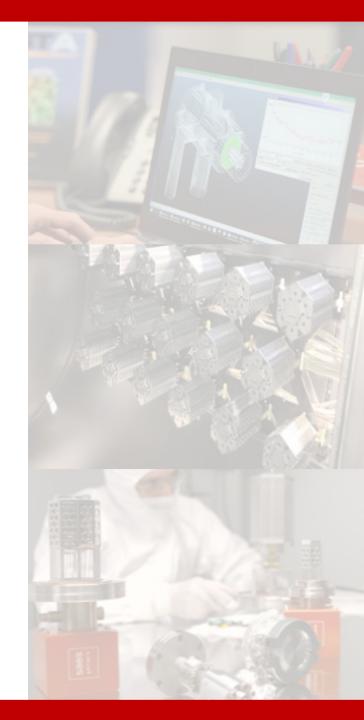
Temkin isotherm: pump-down predictions w/ or w/o bake-out





Particle detection





Particle detection system



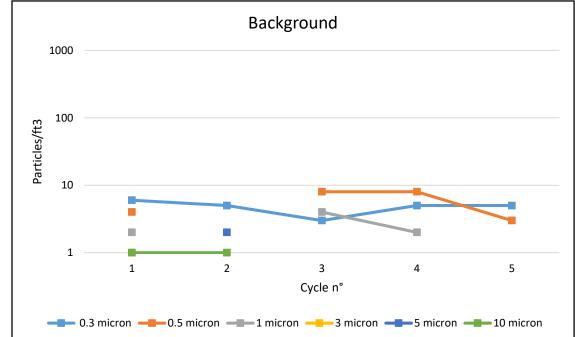


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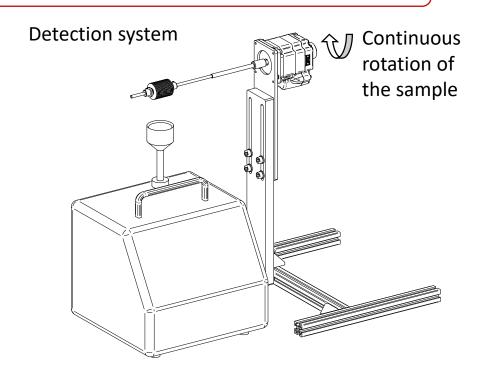


Robust particle detection system:

- Implemented in ISO 6 cleanroom.
- Repeatable measurements.
- Minimization of background effects.
- Capability to check the effectiveness of cleaning treatments developed in our labs.

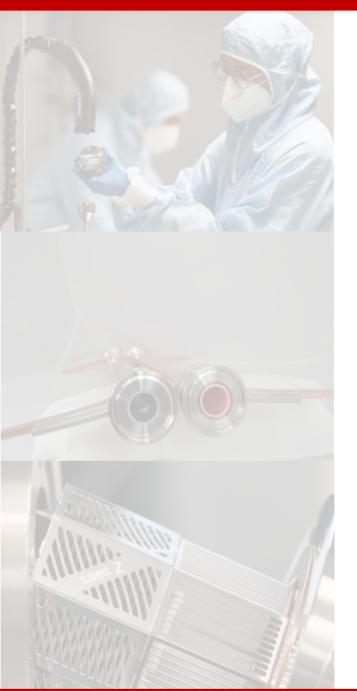


Checking the effectiveness of cleaning treatments Untreated sample 1000 Particles/ft3 100 10 1 Cycle n° Untreated - 0.3 micron — Untreated - 0.5 micron — Untreated - 1 micron Untreated - 3 micron Untreated - 10 micron **Treated sample** 1000 Particles/ft3 100 10 saes 2 3 5 Cycle n° Treated - 0.3 micron — Treated - 0.5 micron — Treated - 1 micron making innovation happen, together



Example of countings for 11 dsk NEG stacks (ZAO UHV):

- Treated stack: background-comparable; ٠ masses > 5 micron below 2 units at the first minute, then they are not detected anymore.
- Effectiveness of cleaning treatment. •



Thank you for your attention



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